

SU-8 2050 – run sheet

Kayaku Advanced Materials

nanyte.com/photoresists/su-8-2050 · last updated 2026-07-26

Thickness: 40.1–171 μm

Softbake: 95 °C · hotplate

Exposure dose – dose by film thickness

Film thickness	Dose
25–40 μm	150–160 mJ/cm^2
45–80 μm	150–215 mJ/cm^2
85–110 μm	215–240 mJ/cm^2
115–150 μm	240–260 mJ/cm^2
160–225 μm	260–350 mJ/cm^2
230–270 μm	350–370 mJ/cm^2

Post-exposure bake: 95 °C

Develop: Developer SU-8 Developer (Kayaku's proprietary PGMEA-based developer); other solvent developers such as ethyl lactate or diacetone alcohol are also stated to work · Dilution undiluted · Rinse Fresh SU-8 developer spray/wash ~10 s, optionally repeated, then air/N₂ dry with filtered pressurized gas. A white film during an IPA rinse indicates under-development of the unexposed resist -- treat with more SU-8 developer and repeat, rather than relying on IPA to finish the job. Ultrasonic/megasonic agitation is recommended for high-aspect-ratio or tight-pitch structures. · Method immersion (spray or spray-puddle also usable per datasheet)

Hardbake: 150–250 °C · 5–30 min